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| **AUTHOR:** | **CHECKED:** | **DATE** | **APPROVALS** |
| **DCN NO.**  | **REV** | **DATE** |
| **E. Hirose** |  | **Jan09-12** |  | **V2** | **Jan09-12** |
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**Applicable Documents**

LCGT-MIR-D00003-V1 Fused Silica Substrate, LCGT Beam Splitter

**Requirements**

**Physical Configuration**

According to LCGT-MIR-D00003-V1 Fused Silica Substrate, LCGT Beam Splitter

**Fabricate from**

Fused Silica Blank will be prepared for this Beam Splitter

## Registration Marks

Registration marks shall be etched, ground or sandblasted and located per LCGT-MIR-D00003-V1

## Surfaces, Side and Bevel Polish

All Surfaces, Sides and Bevels shall be polished using a progression of smaller grit sizes. The last step before final polish shall be equal to or less than a five micrometer grit finish. These surfaces shall appear transparent with no grey, scuffs or scratches visible to the naked eye when viewed in normal room light against a black background.

**Bevel**

Bevel for safety per LCGT-MIR-D00003-V1

## Serial Number

Serial Number “BS XX” shall be etched, ground or sandblasted on the barrel of the optic per LCGT-MIR-D00003-V1, where X is incremental starting with 01.

**Scratches, Sleeks and Point defects**

Point defects of radius greater than 25 micrometers are treated like scratches for the purpose of this specification.

**Scratches and Sleeks, Surfaces 1 and 2**

The total area of scratches and sleeks on the entire surface shall not exceed 500 X 103 square micrometers (width times length.)

**Point Defects, Surfaces 1 and 2**

There shall be no more than 50 point defects of radius greater than 2 m on the entire surface on each surface. Average density of defects less than 2m radius must be less than or equal to 5 per 4mm2

**Scratch and Point Defect Inspection Method**

1. The surface is examined visually by two observers independently. The examination is done against a dark background using a fiber optic illumination system of at least 200 W total power. A 100% inspection of the surface is carried out. Pits and scratches down to 2 micrometers in width can be detected using this method of inspection. Any scratches or sleeks that are detected will be measured using a calibrated eyepiece.

2. Further inspection will be done with a minimum 6X eyeglass using the same illumination conditions, again with two observers. Sleeks down to 0.5 micrometers wide can be detected using this method. The surface will be scanned along one or two chords from centre to edge, then at ten positions around the edge, and ten to fifteen positions near the centre.

3. An inspection is then carried out with a dark or bright field microscope, with 5x objective at four positions at each of the following locations:

1. Within 10mm of the center of the surface.
2. Equally spaced along the circumference of a centered, 60 mm diameter circle.
3. Equally spaced along the circumference of a centered, 120 mm diameter circle

**Surface Figure, measured over the central 220mm diameter**

**Surface 1:** Nominally Flat. Radius of curvature: Flat > 300 Km concave, >1000 Km convex
Astigmatism: < 8 nm Amplitude of the Zernike coefficient Z2, 2 as defined in Born and Wolf pp. 523-525.

**Surface 2:** Nominally flat. Surface two should be polished such that the Radius of curvature of Surface 1 as measured through Surface 2 and the material is > | 300 Km|

**Surface Error, Low Spatial Frequency: measurement aperture to 1 mm-1**

The following root mean square standard deviation (σrms) values are calculated from the phase maps which are to be provided with each optic. For this calculation the amplitudes for the best fit Zernike terms Z0,0, Z1,1, Z2,0 and Z2,2 or corresponding Seidel aberrations are subtracted from the phase map. Known bad pixels may be excluded from this calculation.

Surface 1, Frequency Band: < 1 mm -1Measured over the central 220 mm diameter aperture: σrms < 3 nanometers
Measured over the central 200 mm diameter aperture: σrms < 2 nanometers

Surface 2 - Frequency Band: < 1 mm -1Measured over the central 220 mm diameter aperture: σrms < 4 nanometers
Measured over the central 200 mm diameter aperture: σrms < 2 nanometers

**Error, High Spatial Frequency: 1– 750 mm -1**

Surface 1 HSF error σrm**s** < 0.3 nanometers measured at the following locations:
1. Within 2mm of the center of the surface.
2. Four positions equally spaced along the circumference of a centered, 60 mm diameter circle.
3. Three positions equally spaced along the circumference of a centered, 120 mm diameter circle.

Surface 2 HSF error σrm**s** < 0.5 nanometer measured at the following location:
1. Within 2mm of the center of the surface.

**Inspection**

1. **Table 1: Inspections**

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| Specification  | Test Method and frequency | Data Delivered  |
| Dimensions | Measurement100%  | Measurement Results |
| Scratches and Point defects methods 1 and 2  | Visual Inspection100%  | Hand sketch including scratch/pit dimensions  |
| Scratches and Point defects method 3 | Visual Inspection100% | Digital image of each inspection location |
| Figure | Interferometry 100% | Surface phase maps  |
| Errors - Low Spatial Frequency  | Interferometry 100% | Surface phase maps |
| Errors - High Spatial Frequency  | Interferometry 100% | Surface maps for 3 central locations. Numerical values included with certification  |

Orientation: For the purpose of full surface phase maps the data shall be oriented such that the substrate registration mark is at the top center of the data.

Format: All Data shall be delivered according to Table 1. In addition to the hard copy, an electronic data set of the phase maps shall be delivered in ASCII.